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⑮ 発明の名称 固体発光素子

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明細書

1. 発明の名称

固体発光素子

2. 特許請求の範囲

(1) 微量なBeを含むP形堿化ホウ素結晶層及びこの結晶層上に形成された微量なSiを含むN形堿化ホウ素結晶層からなる基体と、少なくともこの基体の側部の前記P形、N形堿化ホウ素結晶層の接合面を覆う粒径0.3~1.3μmから構成された粒状の螢光体層と、前記基体の上面、下面に夫々形成された電極とを具備することを特徴とする固体発光素子。

(2) 微量なBeを含むP形堿化ホウ素結晶層及びこの結晶層上に形成された微量なSiを含むN形堿化ホウ素結晶層からなる基体と、少なくともこの基体の側部の前記P形、N形堿化ホウ素結晶層の接合面を覆う膜厚0.6~2.8μmの薄膜螢光体層と、前記基体の上面、下面に夫々形成された電極とを具備することを特徴とする固体発光素子。

3. 発明の詳細な説明

【発明の目的】

(産業上の利用分野)

本発明は、P-N接合面を有する固体発光素子の改良に関する。

(従来の技術)

近年、エレクトロニクス技術の進展に伴い発光素子も放電管を用いたものばかりでなく、固体発光素子が広く用いられつつある。

従来、固体発光素子の代表的なものとしては、例えば第2図示す如く、N形GaP結晶基板1上にTeを微量含むN形GaPエピタキシャル層2及び微量のZn、Oを含むP形GaPエピタキシャル層3を形成させ、更にこのP形GaPエピタキシャル層3上及び前記基板1の裏面に夫々電極4、5を形成した構造の赤色発光素子が知られている。また、この他図示しないが、N型GaAs基板にGaAsP、GaAlAsのPN接合を利用した赤色発光素子、前記基板上におけるGaAs_{1-x}P_xのPN接合を利用した橙、黄色発光素

子、前記GaN上におけるGaNのPN接合を利用した緑色発光素子、SiC上のSiCのPN接合を利用した青色発光素子等が知られている。

しかし、これらの固体発光素子は、小型で電子回路との整合性が良いという利点の反面、夫々の種類の発光素子特有の発光波長に規制され、それ以外の発光色を選択しても、固体発光素子の種類自体も少なく、任意の発光色を得ることが困難であった。

(発明が解決しようとする課題)

本発明は上記事情に鑑みてなされたもので、様々な発光色をもちらしながら同一種類のPN接合を有する固体発光素子を提供することを目的とする。

[発明の構成]

(課題を解決するための手段)

本願第1の発明は、微量なBeを含むP形塗化ホウ素結晶層及びこの結晶層上に形成された微量なSiを含むN形塗化ホウ素結晶層からなる基体と、少なくともこの基体の側部の前記P形、N

した場合、第3図に示す如く、主に200～400nmの紫外域にピーク波長を有する発光スペクトルを得た。そこで、本発明者等はPN接合上に粒径や膜厚の異なる様々な蛍光体層を形成させて実験を試みたところ、上記に記載した発明を得るに至ったものである。

以下、本発明について第1図を参照して更に詳しく説明する。

図中の11は、微量なBeを含むP形塗化ホウ素結晶層(以下、P形層といふ)である。このP形層11上には、微量なSiを含むN形塗化ホウ素結晶層(以下、N形層といふ)12が形成されている。ここで、前記P形層11とN形層12を総称して基体と呼ぶ。この基体の側壁には、粒径0.3～13μmの粒から構成された粒状の蛍光体層13が形成されている。なお、この蛍光体層13は、基体の側壁全体に亘って形成されている必要はなく、少なくともP形層11とN形層12の接合部分を覆っていればよい。前記基体の上面、下面には、夫々電極14、15が形成されている。

形塗化ホウ素結晶層の接合面を覆う粒径0.3～13μmの粒から構成された粒状の蛍光体層と、前記基体の上面、下面に夫々形成された電極とを具備することを特徴とする固体発光素子である。

本願第2の発明は、微量なBeを含むP形塗化ホウ素結晶層及びこの結晶層上に形成された微量なSiを含むN形塗化ホウ素結晶層からなる基体と、少なくともこの基体の側部の前記P形、N形塗化ホウ素結晶層の接合面を覆う膜厚0.6～2.6μmの薄膜蛍光体層と、前記基体の上面、下面に夫々形成された電極とを具備することを特徴とする固体発光素子である。

本願第1の発明において、粒状の蛍光体層を構成する粒径が0.3～13μmの範囲を外れると、十分な発光強度が得られない。また、本願第2の発明においても、蛍光体層の膜厚が0.6～2.6μmの範囲を外れると、十分な発光強度が得られない。

本発明者等は、上記蛍光体層を形成する前、即ち順バイアス方向に例えば0.5mAの電流を流

(作用)

本発明によれば、PN接合上に粒径や膜厚の異なる様々な蛍光体層を形成させることにより、様々な発光色をもちらしながら同一種類のPN接合を有する固体発光素子を得ることができる。

(実施例1)

自己付活蛍光体MgWO₄を、ニトロセルロース6wt%、エタノール2.5wt%、ブチルアセテート86.5wt%、ジエチルフタレート5.0wt%からなる溶液に搅拌、混合した。次に、このMgWO₄粒子を前述したPN接合部分を含む基体側壁に空気中400℃に加熱後、室温に冷却して蛍光体層を形成し、固体発光素子を得た。

こうして得られた固体発光素子に順バイアス方向に電圧20V、電流2mAを流したところ、480nmにピーク波長が存在する発光スペクトルが得られ、青色発光を示した。また、粒径の異なるMgWO₄粉体蛍光体層をPN接合部分に上記と同様な方法で夫々形成させて発光スペクトル

を測定し、480nm のピーク波長における相対発光強度を求め、第4図に示す相対発光強度と蛍光体粒径との関係を求めた。同図により、蛍光体粒径が0.6μm以下の場合、蛍光体の発光効率が極めて悪く、最大発光強度が得られる蛍光体粒径4.0μm前後の発光強度に比較して20%以下に低下し、ほとんど発光に対する寄与はなかった。一方、蛍光体粒径が11μm以上の場合も同様に相対発光強度は20%以下に低下し、発光に対する寄与は少なかった。以上より、蛍光体層を構成するMgWO₄の粒径は0.6~11μmが好ましい。

(実施例2)

自己付活蛍光体CaWO₄を試料粉末として実施例1と同様に、有機溶液中に分散、攪拌混合した。次に、このCaWO₄粒子を前述したPN接合部分を含む基体側壁に塗布し乾燥後470°Cに加熱し、室温に冷却して蛍光体層を形成し、固体発光素子を得た。

こうして得られた固体発光素子に順バイアス方

こう、525nmにピーク波長を有する発光スペクトルが得られ、緑色発光を示した。

また、蛍光体粒径を変化させ、第6図に示す相対発光強度と蛍光体粒径との関係を求めた。同図により、蛍光体粒径が5μmの付近で最大の発光強度が得られたが、粒径が1.3μm以下または13μm以上になると、相対発光強度が20%以下に低下し、発光への寄与はなかった。従って、こうした蛍光体を使用した場合、蛍光体粒径は、1.3~13μmが好ましい。

(実施例4)

蛍光体Y₂O₃:Euを使用して実施例1と同様な方法でこの粒子からなる蛍光体層をPN接合部分を含む基体側壁に塗布して蛍光体層を形成し、固体発光素子を得た。

こうして得られた固体発光素子に順バイアス方向に電極間電圧30V、電流3.0mAを流したところ、611nmにピーク波長を有する発光スペクトルが得られ、緑色発光を示した。

また、蛍光体粒径を変化させ、第7図に示す相

向に電極間電圧30V、電流3mAを流したところ、415nm前後にピーク波長を持つ発光スペクトルが得られ、青色発光を示した。

また、粒径の異なるCaWO₄粉体蛍光体層をPN接合部分に上記と同様な方法で夫々形成させて発光スペクトルを測定し、480nmのピーク波長における相対発光強度を求め、第5図に示す相対発光強度と蛍光体粒径との関係を求めた。同図により、蛍光体粒径が6μmの付近で最大の発光強度が得られたが、MgWO₄場合と同様、粒径が2μm以下または13μm以上になると、20%以下に低下した。従って、CaWO₄蛍光体を使用した場合、蛍光体粒径は、2~13μmが好ましい。

(実施例3)

蛍光体Zn₂SiO₄:Mnを使用して実施例1と同様な方法でこの粒子からなる蛍光体層をPN接合部分を含む基体側壁に塗布して蛍光体層を形成し、固体発光素子を得た。

こうして得られた固体発光素子に順バイアス方向に電極間電圧25V、電流2.5mAを流したと

対発光強度と蛍光体粒径との関係を求めた。同図により、蛍光体粒径が4.2μmの付近で最大の発光強度が得られたが、粒径が0.7μm以下または11μm以上になると、相対発光強度が20%以下に低下し、発光への寄与はなかった。従って、こうした蛍光体を使用した場合、蛍光体粒径は、0.7~11μmが好ましい。

(実施例5)

自己付活蛍光体MgWO₄を真空ベルジャ内に入れ、真空中度を $1 \times 10^{-6} \sim 5 \times 10^{-6}$ Pa Hg程度にする。この状態でArガスを導入し、2.10~2.10Pa Hg Ar雰囲気中でMgWO₄粉末をスパッタ、同じく真空ベルジャ内のMgWO₄粉末と反対側に設置したPN接合部分に所望の厚みの蛍光体層をスパッタリング法により形成し、固体発光素子を得た。

こうして得られた固体発光素子に順バイアス方向に電極間電圧20V、電流2mAを流したところ、480nmにピーク波長が存在する発光スペクトルが得られ、青色発光を示した。また、膜厚の異

なる $MgWO_4$ 薄膜蛍光体層を P-N 接合部分に上記と同様な方法で夫々形成させて発光スペクトルを測定し、480nm のピーク波長における相対発光強度を求め、第8図に示す相対発光強度と蛍光体粒径との関係を求めた。同図により、蛍光体粒径が 0.6 μm 以下の場合、蛍光体の発光効率が極めて悪く、最大発光強度が得られる蛍光体粒径 1 μm 前後の発光強度に比較して 20% 以下に低下し、ほとんど発光に対する寄与はなかった。一方、蛍光体粒径が 2.6 μm 以上の場合も同様に相対発光強度は 20% 以下に低下し、発光に対する寄与は少なかった。以上より、蛍光体層を構成する $MgWO_4$ の粒径は 0.6 ~ 2.6 μm が好ましい。

(実施例 6)

自己付活蛍光体 $CaWO_4$ を試料粉末として実施例 5 と同様に、真空スパッタリング法にて $CaWO_4$ 粒子を前述した P-N 接合部分を含む基体側壁に塗布して蛍光体層を形成し、固体発光素子を得た。

こうして得られた固体発光素子に順バイアス方向に電極間電圧 25V、電流 2.5 mA を流したところ、525nm にピーク波長を有する発光スペクトルが得られ、緑色発光を示した。

また、蛍光体層の膜厚を変化させ、第10図に示す相対発光強度と蛍光体粒径との関係を求めた。同図により、蛍光体層の膜厚が 1.4 μm の付近で最大の発光強度が得られたが、膜厚が 0.4 μm 以下または 3.0 μm 以上になると、相対発光強度が 20% 以下に低下し、発光への寄与は少なかった。従って、こうした蛍光体を使用した場合、蛍光体粒径は、0.4 ~ 3.0 μm が好ましい。

(実施例 8)

蛍光体 $Y_2O_3:Eu$ を使用して実施例 5 と同様な方法でこの粒子からなる蛍光体層を P-N 接合部分を含む基体側壁に塗布して蛍光体層を形成し、固体発光素子を得た。

こうして得られた固体発光素子に順バイアス方向に電極間電圧 30V、電流 3.0 mA を流したと

こうして得られた固体発光素子に順バイアス方向に電極間電圧 30V、電流 3 mA を流したところ、415nm 前後にピーク波長を持つ発光スペクトルが得られ、青色発光を示した。

また、膜厚の異なる $CaWO_4$ 粉体蛍光体層を P-N 接合部分に上記と同様な方法で夫々形成させて発光スペクトルを測定し、ピーク波長における相対発光強度を求め、第9図に示す相対発光強度と蛍光体粒径との関係を求めた。同図により、蛍光体粒径が 1.6 μm 付近で最大の発光強度が得られたが、 $MgWO_4$ の場合と同様、膜厚が 0.6 μm 以下または 2.6 μm 以上になると、20% 以下に低下した。従って、 $CaWO_4$ 蛍光体を使用した場合、蛍光体粒径は、0.6 ~ 2.6 μm が好ましい。

(実施例 7)

蛍光体 $Zn_2SiO_4: Mn$ を使用して実施例 5 と同様な方法でこの粒子からなる蛍光体層を P-N 接合部分を含む基体側壁に塗布して蛍光体層を形成し、固体発光素子を得た。

こうして得られた固体発光素子に順バイアス方向に電極間電圧 25V、電流 2.5 mA を流したところ、511nm にピーク波長を有する発光スペクトルが得られ、緑色発光を示した。

また、蛍光体層の膜厚を変化させ、第11図に示す相対発光強度と蛍光体粒径との関係を求めた。同図により、1 μm 前後で最大発光強度がえられたが、その膜厚が 0.3 μm 以下または 3.0 μm 以上になると、相対発光強度が 20% 以下に低下し、発光への寄与は少なかった。従って、こうした蛍光体を使用した場合、蛍光体粒径は、0.3 ~ 3.0 μm が好ましい。

[発明の効果]

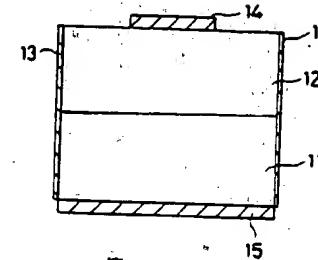
以上詳述した如く本発明によれば、様々な発光色をもちらしながらも同一種類の P-N 接合を有する信頼性の高い固体発光素子を提供できる。

4. 図面の簡単な説明

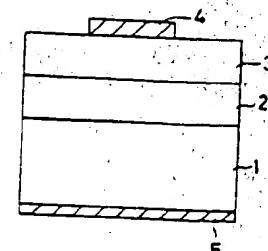
第1図は本発明の一実施例に係る固体発光素子の断面図、第2図は従来の固体発光素子の断面図、第3図は本発明に係る固体発光素子の P-N 接合面からの放射光の発光スペクトル特性図、第4図~第7図は夫々異なる粒径の粉体蛍光体による

相対発光強度と発光体粒径との関係を示す特性図、第8図～第11図は夫々異なる膜厚の層膜蛍光体粒子による相対発光強度と発光体膜厚との関係を示す特性図である。

11-P形窒化ホウ素結晶層、12-NP形窒化ホウ素結晶層、13-蛍光体層、14、15-電極。

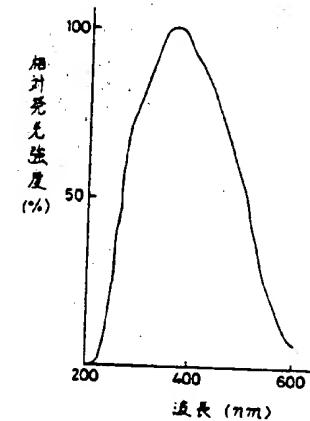


第1図

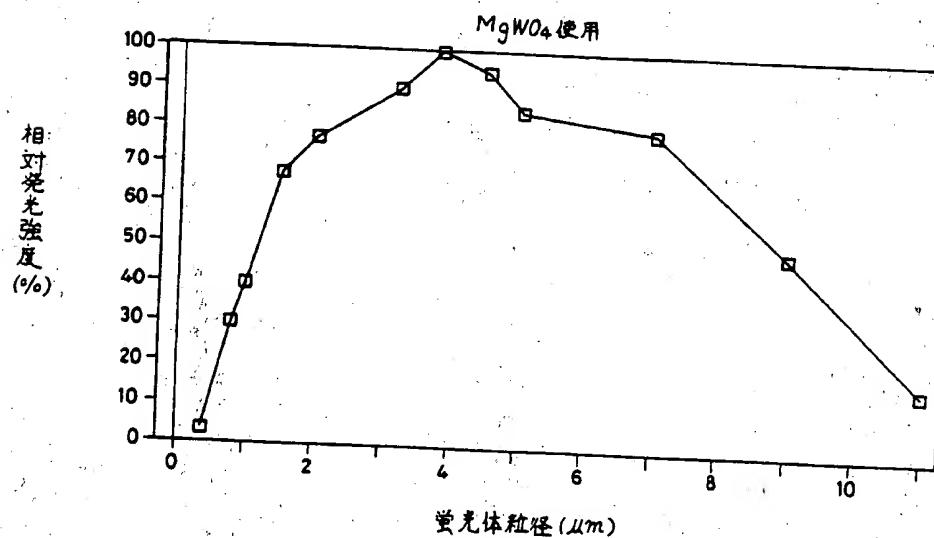


第2図

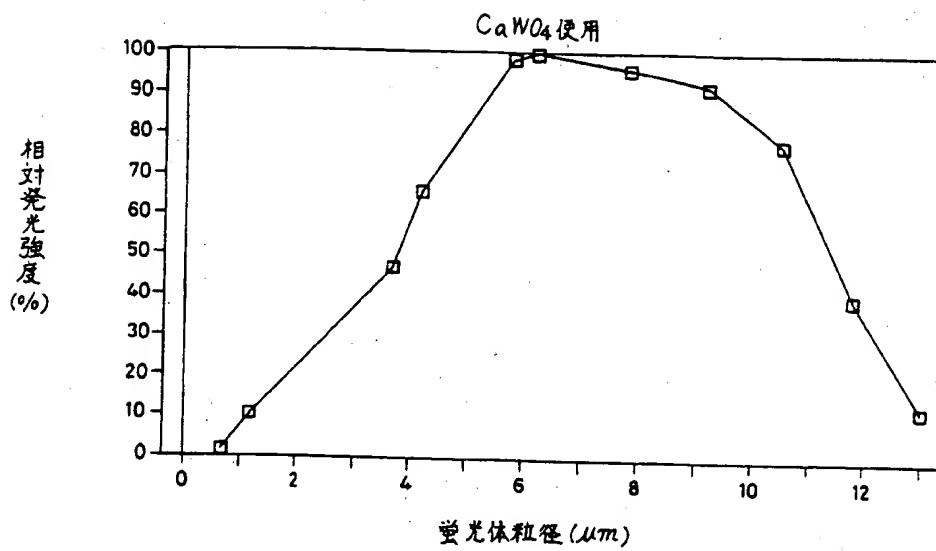
出願人代理人弁理士 鈴江武彦



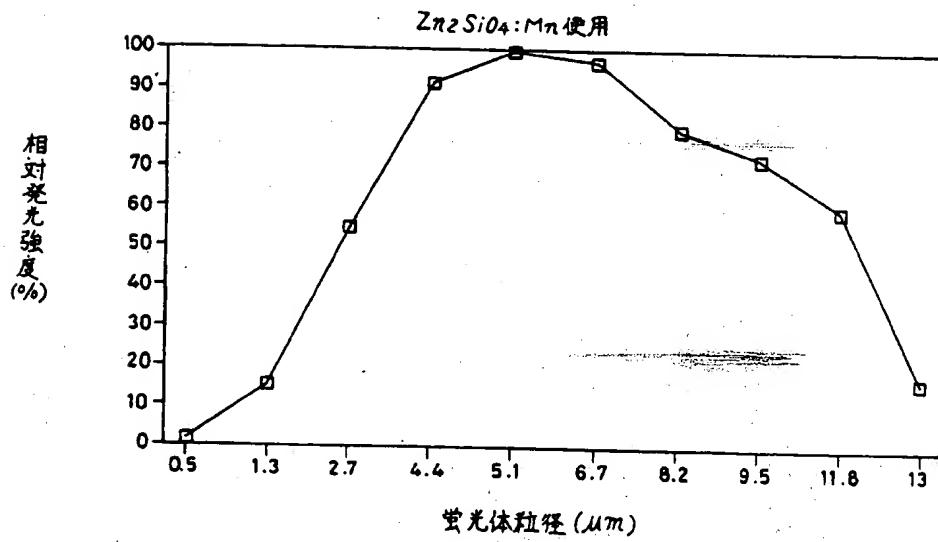
第3図



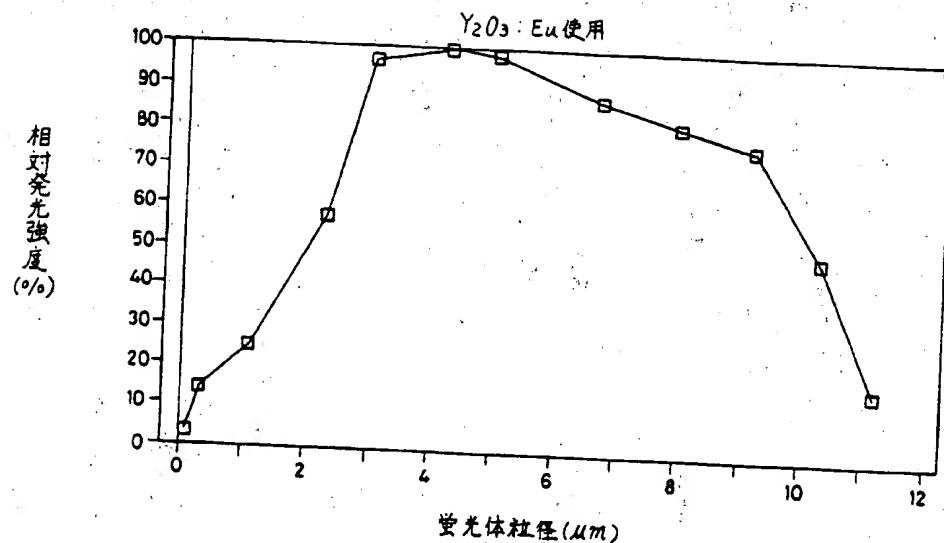
第4図



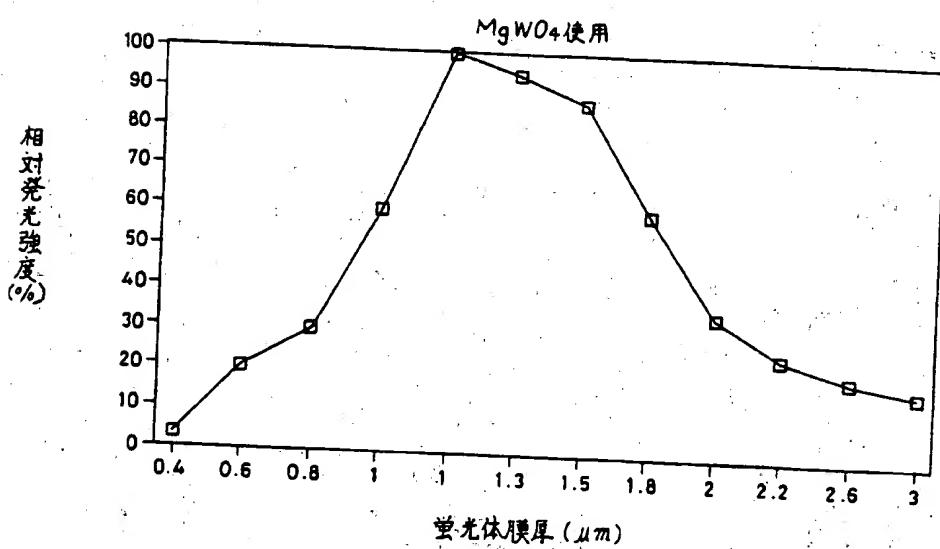
第 5 図



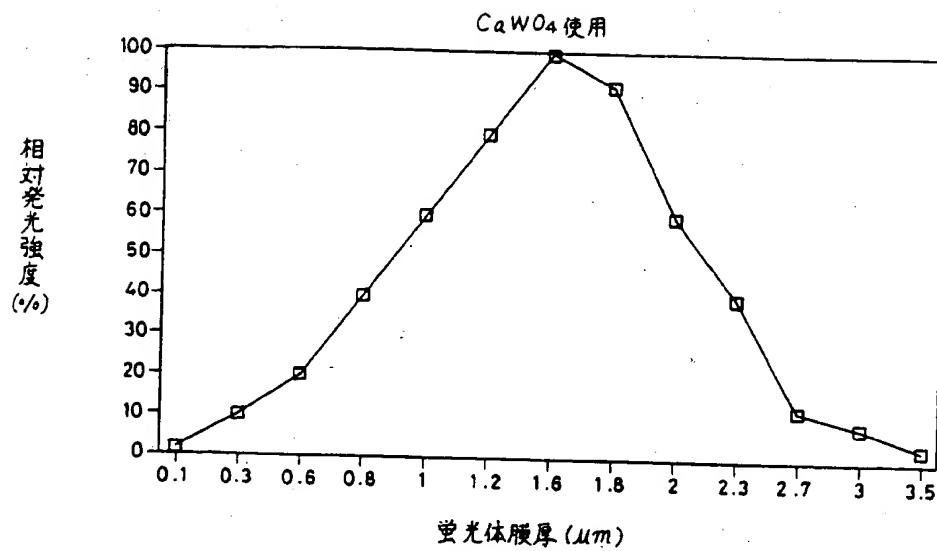
第 6 図



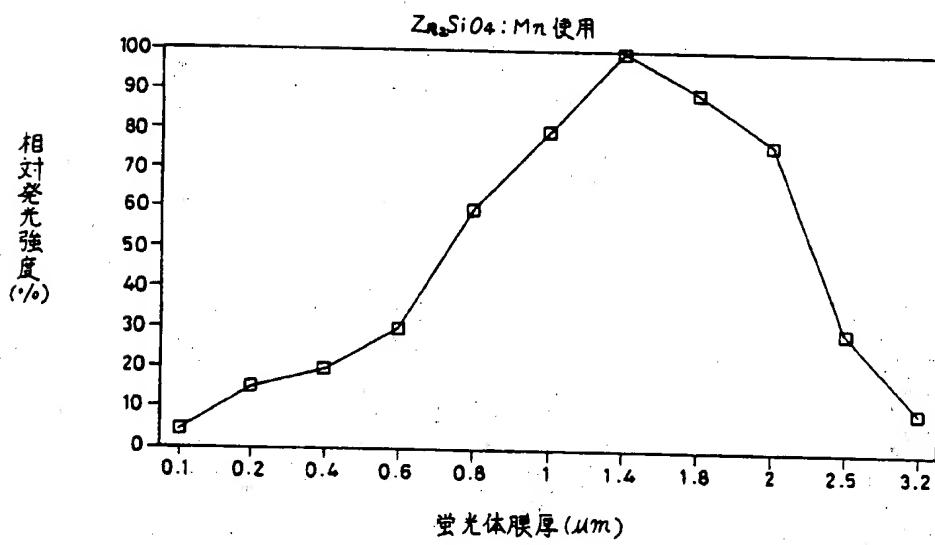
第 7 図



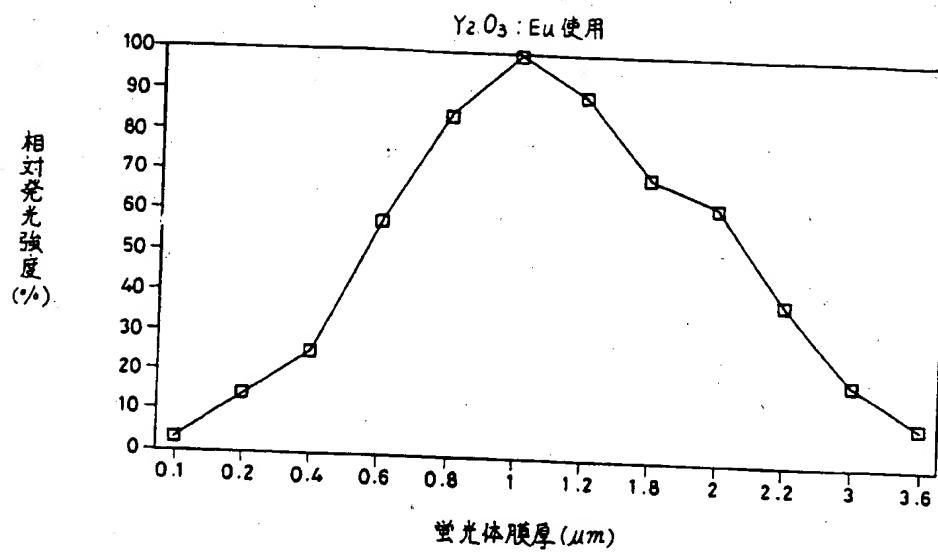
第 8 図



第 9 図



第 10 図



第 11 図

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Translation of

Japanese Laid-open (Kokai) Patent Application HEI 2-91980 (A)

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1. Title of the invention

Solid-state light emitting element

2. What is claimed is:

(1) A solid-state light emitting element, characterized by comprising a substrate made up of a p-type boron nitride crystal layer including a minute amount of Be, and an n-type boron nitride crystal layer formed on the said crystal layer and including a minute amount of Si; a layer of particulate phosphor with a particle size of 0.3 - 13 μm which covers at least the junction interface of said p-type and n-type boron nitride crystal layers on the side portions of said substrate; and electrodes respectively formed on an upper surface and a lower surface of said substrate.

(2) A solid-state light emitting element, characterized by comprising a substrate made up of a p-type boron nitride crystal layer including a minute amount of Be, and an n-type boron nitride crystal layer formed on the said crystal layer and including a minute amount of Si; a thin-film phosphor layer with a film thickness of 0.6 - 2.6 μm which covers at least the junction interface of said p-type and n-type boron nitride crystal layers on the side portions of said substrate, and electrodes respectively formed on an upper surface and a lower surface of said substrate.

3. Detailed description of the invention

Object of the invention

Field of industrial application

The present invention relates to an improvement to solid-state light emitting elements having a pn junction interface.

Prior art

As a result of technological advances in electronics over the recent years, not only discharge tubes are used any more as light-emitting elements, but solid-state light emitting elements are finding an increasingly wide use.

As a prior art representative for solid-state light emitting elements there is known, for example, a red light emitting element as shown in Fig. 2 and having the following structure: on an n-type GaP crystal substrate 1, an n-type GaP epitaxial layer 2 including a minute amount of Te and a p-type GaP epitaxial layer 3 including a minute amount of Zn and O are formed; furthermore electrodes 4, 5 are respectively formed on this p-type GaP epitaxial layer 3 and on the rear surface of the substrate 1. Apart from this, though not pictorially represented, there are also known red light emitting elements using a pn junction of GaAsP and GaAlAs on an n-type GaAs substrate; orange and yellow light emitting elements using a pn junction of $GeAs_{1-x}P_x$ on the said substrate; green light emitting elements using a pn junction of GaP on the said GaP; blue light emitting elements using a pn junction of SiC on SiC.

Despite their advantages of a small size and good consistency with electronic circuitry, these solid-state light emitting elements were nevertheless limited to the emission wavelengths that are characteristic for the respective types of light-emitting elements; even if light emission of another color were to be selected, the very types of solid-state light emitting elements are few, and light emission having a desired color was difficult to achieve.

Problems to be solved by the invention

The present invention was conceived before the background of this situation with the purpose of furnishing a solid-state light emitting element providing various colors of emitted light while having the same kind of pn junction.

Constitution of the invention

Measures for achieving the object

The first invention of the present application is a solid-state light emitting element which is characterized by comprising a substrate made up of a p-type boron nitride crystal layer including a minute amount of Be, and an n-type boron nitride crystal layer formed on the said crystal layer and including a minute amount of Si; a layer of particulate phosphor with a particle size of 0.3 - 13 μm which covers at least the

junction interface of the p-type and n-type boron nitride crystal layers on the side portions of the substrate; and electrodes respectively formed on an upper surface and a lower surface of the substrate.

The second invention of the present application is a solid-state light emitting element which is characterized by comprising a substrate made up of a p-type boron nitride crystal layer including a minute amount of Be, and an n-type boron nitride crystal layer formed on the said crystal layer and including a minute amount of Si; a thin-film phosphor layer with a film thickness of 0.6 - 2.6 μm which covers at least the junction interface of the p-type and n-type boron nitride crystal layers on the side portions of the substrate, and electrodes respectively formed on an upper surface and a lower surface of the substrate.

In the first invention of the present application, when the size of the particles of which the layer of particulate phosphor is composed, is outside the range of grain sizes between 0.3 and 13 μm , it is not possible to achieve a sufficient emission intensity. Also in the second invention of the present application, when the film thickness of the phosphor layer is outside the range of 0.6 to 2.6 μm , it is not possible to achieve a sufficient emission intensity.

When the present inventors applied a forward-biased current of, e.g., 0.5 mA prior to forming the said phosphor layer, a light emission spectrum having a peak wavelength in the 200 - 400 nm ultraviolet range in accordance with the representation in Fig. 3 was mainly achieved. Thereupon the inventors experimented with forming various phosphor layers having different particle sizes and film thicknesses on the pn junction, whereby they managed to arrive at the above described invention(s).

In the following, the present invention shall be explained in more detail by referring to Fig. 1.

In the figure, 11 denotes a p-type boron nitride crystal layer including a minute amount of Be (hereinafter: p-type layer). On this p-type layer 11, an n-type boron nitride crystal layer 12 including a minute amount of Si (hereinafter: n-type layer) is formed. For the present purposes, this p-type layer 11 and n-type layer 12 shall jointly be referred to as the substrate. On the side walls of this substrate, a particulate phosphor layer 13 comprised of particles having particle sizes of 0.3 - 13 μm is formed. There is no need to form this phosphor layer 13 so as to extend over the entire side wall, but it is

sufficient if it at least covers the junction portion of p-type layer 11 and n-type layer 12. Electrodes 14, 15 are respectively formed on the upper and lower surfaces of the substrate.

Function

Through the formation of various phosphor layers of different particle sizes and film thicknesses, the present invention makes it possible to obtain solid-state light emitting elements with the same kind of pn junction that provide various colors of emitted light.

First embodiment

A self-activating phosphor $MgWO_4$ was mixed into a solution of 6% (wt.) of nictrocellulose, 2.5% (wt.) of ethanol, 86.5% (wt.) of butyl acetate, 5.0% (wt.) of diethyl phthalate by stirring. Then a solid-state light emitting element was obtained by applying these $MgWO_4$ particles on the substrate side walls including the above mentioned pn junction portion, heating to 400°C, and then cooling to room temperature so as to form the phosphor layer.

When a forward-biased current of 2 mA having a voltage of 20 V was applied between the electrodes of the solid-state light emitting element obtained in this way, a light emission spectrum having a peak wavelength at 480 nm was obtained which exhibited a blue light emission. Furthermore phosphor layers of $MgWO_4$ powder of various particle sizes were respectively formed on the pn junction portions by the same method as set forth above, the light emission spectrum was measured, the relative emission intensities at the peak wavelength of 480 nm were determined, and the relationship between relative emission intensity and phosphor particle size as shown in Fig. 4 was determined. In accordance with this figure, when the phosphor particle size was 0.6 μm or less, the luminous efficiency of the phosphor was extremely poor and was reduced to less than 20% in comparison with a phosphor particle size of about 4.0 μm at which a maximum emission intensity was obtained, and there was hardly any contribution to light emission. With phosphor particle sizes of 11 μm and more, on the other hand, the relative emission intensity was equally reduced to less than 20%, so that the contribution to light emission was small. In accordance with the above, a particle size of 0.6 - 11 μm is preferred for the $MgWO_4$ making up the phosphor layer.

Second embodiment

A self-activating phosphor CaWO_4 as the test powder was dispersed in an organic solution in the same way as in the first embodiment and mixed by stirring. Then a solid-state light emitting element was obtained by applying these MgWO_4 particles on the substrate side walls including the above mentioned pn junction portion, heating to 470°C, and then cooling to room temperature so as to form the phosphor layer.

When a forward-biased current of 3 mA having a voltage of 30 V was applied between the electrodes of the solid-state light emitting element obtained in this way, a light emission spectrum having a peak wavelength at about 415 nm was obtained which exhibited a blue light emission.

Furthermore phosphor layers of CaWO_4 powder of various particle sizes were respectively formed on the pn junction portion by the same method as set forth above, the light emission spectrum was measured, the relative emission intensities at the peak wavelength of 480 nm were determined, and the relationship between relative emission intensity and phosphor particle size as shown in Fig. 4 was determined. In accordance with this figure, a maximum emission intensity was obtained with a phosphor particle size in the vicinity of 6 μm , however just as in the case of MgWO_4 , with particle sizes of 2 μm or less or 13 μm or more it was reduced to less than 20%. Accordingly, a phosphor particle size of 2 - 13 μm is preferred when using CaWO_4 phosphor.

Third embodiment

A solid-state light emitting element using $\text{Zn}_2\text{SiO}_4 : \text{Mn}$ phosphor was obtained by the same method as in the first embodiment by applying this particulate phosphor layer on the substrate side walls including the pn junction portion so as to form the phosphor layer.

When a forward-biased current of 2.5 mA having a voltage of 25 V was applied between the electrodes of the solid-state light emitting element obtained in this way, a light emission spectrum having a peak wavelength at 525 nm was obtained which exhibited a green light emission.

Furthermore the relationship between relative emission intensity and phosphor particle size as shown in Fig. 6 was determined by varying the phosphor particle sizes. In accordance with this figure, a maximum emission intensity was obtained with a phosphor particle size in the vicinity of 5 μm , however when the particle size became 1.3 μm or less or 13 μm or more, the relative emission intensity was reduced to less than

20%, and there was no contribution to light emission. Accordingly, a phosphor particle size of 1.3 - 13 μm is preferred when using such a phosphor.

Fourth embodiment

A solid-state light emitting element using $\text{Y}_2\text{O}_3 : \text{Eu}$ phosphor was obtained by the same method as in the first embodiment by applying this particulate phosphor layer on the substrate side walls including the pn junction portion so as to form the phosphor layer.

When a forward-biased current of 3.0 mA having a voltage of 30 V was applied between the electrodes of the solid-state light emitting element obtained in this way, a light emission spectrum having a peak wavelength at 611 nm was obtained which exhibited a green light emission.

Furthermore the relationship between relative emission intensity and phosphor particle size as shown in Fig. 7 was determined by varying the phosphor particle sizes. In accordance with this figure, a maximum emission intensity was obtained with a phosphor particle size in the vicinity of 4.2 μm , however when the particle size became 0.7 μm or less or 11 μm or more, the relative emission intensity was reduced to less than 20%, and there was no contribution to light emission. Accordingly, a phosphor particle size of 0.7 - 11 μm is preferred when using such a phosphor.

Fifth embodiment

A self-activating phosphor MgWO_4 was placed in a vacuum bell jar and a vacuum of about $1 \times 10^{-6} - 6 \times 10^{-6}$ mm Hg was adjusted. Under this condition, Ar gas was introduced, and MgWO_4 powder was sputtered in Ar atmosphere of 2 [?] 10 [?] - 2 [?] 10 [?] mm Hg; in the same way, a phosphor layer having a desired thickness was formed by the sputtering method by sputtering the MgWO_4 powder in the vacuum bell jar on the pn junction portion located on the opposite side, whereby a solid-state light emitting element was obtained.

When a forward-biased current of 2 mA having a voltage of 20 V was applied between the electrodes of the solid-state light emitting element obtained in this way, a light emission spectrum having a peak wavelength at 480 nm was obtained which exhibited a blue light emission. Furthermore MgWO_4 thin-film phosphor layers of various film thicknesses were respectively formed on the pn junction portions by the same method as set forth above, the light emission spectrum was measured, the relative

emission intensities at the peak wavelength of 480 nm were determined, and the relationship between relative emission intensity and phosphor particle size[sic!] as shown in Fig. 8 was determined. In accordance with this figure, when the phosphor particle size was 0.6 μm or less, the luminous efficiency of the phosphor was extremely poor and was reduced to less than 20% in comparison with a phosphor particle size of about 1 μm at which a maximum emission intensity was obtained, and there was hardly any contribution to light emission. With phosphor particle sizes of 2.6 μm and more, on the other hand, the relative emission intensity was equally reduced to less than 20%, so that the contribution to light emission was small. In accordance with the above, a particle size of 0.6 - 2.6 μm is preferred for the MgWO_4 making up the phosphor layer.

Sixth embodiment

A solid-state light emitting element was obtained with a self-activating phosphor CaWO_4 as a the test powder in the same way as in the fifth embodiment, by forming a phosphor layer by applying the GaWO_4 [sic!] phosphor particles on the substrate side walls including the above mentioned pn junction portion by the vacuum sputtering method.

When a forward-biased current of 3.0 mA having a voltage of 30 V was applied between the electrodes of the solid-state light emitting element obtained in this way, a light emission spectrum having a peak wavelength at about 415 nm was obtained which exhibited a blue light emission.

Moreover CaWO_4 [?] powder phosphor layers of various film thicknesses were respectively formed on the pn junction portion by the same method as set forth above, the light emission spectrum was measured, the relative emission intensities at the peak wavelength were determined, and the relationship between relative emission intensity and phosphor particle size[sic!] as shown in Fig. 9 was determined. In accordance with this figure, a maximum emission intensity was obtained in the vicinity of a phosphor grain film thickness of 1.6 μm , however just as in the case of MgWO_4 , with film thicknesses of 0.6 μm or less or 2.6 μm or more it was reduced to less than 20%. Accordingly, a phosphor particle size of 0.6 - 2.6 μm is preferred when using CaWO_4 phosphor.

Seventh embodiment

A solid-state light emitting element using $\text{Zn}_2\text{SiO}_4 : \text{Mn}$ phosphor was obtained by the same method as in the fifth embodiment by applying this particulate phosphor

layer on the substrate side walls including the pn junction portion so as to form the phosphor layer.

When a forward-biased current of 2.5 mA having a voltage of 25 V was applied between the electrodes of the solid-state light emitting element obtained in this way, a light emission spectrum having a peak wavelength at 525 nm was obtained which exhibited a green light emission.

Furthermore the relationship between relative emission intensity and phosphor particle size[sic!] as shown in Fig. 11 was moreover determined by varying the film thickness of the phosphor layer. In accordance with this figure, a maximum emission intensity was obtained in the vicinity of a phosphor layer film thickness of 1.4 μm , however when this film thickness became 0.4 μm or less or 3.0 μm or more, the relative emission intensity was reduced to less than 20%, and there was no contribution to light emission. Accordingly, a particle size of 0.4 - 3.0 μm is preferred when using such a phosphor.

Eighth embodiment

A solid-state light emitting element using $\text{Y}_2\text{O}_3 : \text{Eu}$ was obtained by the same method as in the fifth embodiment by applying this particulate phosphor layer on the substrate side walls including the pn junction portion so as to form the phosphor layer.

When a forward-biased current of 3.0 mA having a voltage of 30 V was applied between the electrodes of the solid-state light emitting element obtained in this way, a light emission spectrum having a peak wavelength at 611 nm was obtained which exhibited a green light emission.

Furthermore the relationship between relative emission intensity and phosphor particle size as shown in Fig. 11 was determined by varying the film thickness of the phosphor layer. In accordance with this figure, a maximum emission intensity was obtained at about 1 μm , however when this film thickness became 0.3 μm or less or 3.0 μm or more, the relative emission intensity was reduced to less than 20%, and there was no contribution to light emission. Accordingly, a phosphor particle size of 0.3 - 3.0 μm is preferred when using such a phosphor.

Effect of the invention

In accordance with the invention as set forth above, it is possible to furnish a highly reliable solid-state light emitting element providing various colors of emitted light while having the same kind of pn junction.

4. Short Explanation of the Drawings

Fig. 1 is a sectional view of a solid-state light emitting element being an embodiment of the present invention,

Fig. 2 is a sectional view of a solid-state light emitting element of the prior art,

Fig. 3 is a diagram showing the characteristic line for the emission spectrum of light radiation from the pn junction interface of a solid-state light emitting element of the present invention,

Fig. 4 - Fig. 7 are characteristic diagrams showing the relation between relative emission intensity and phosphor particle size in respective powder-type phosphors of different particle sizes,

Fig. 8 - Fig. 11 are characteristic diagrams showing the relation between relative emission intensity and phosphor film thickness in respective thin-film phosphors of different film thicknesses.

11 p-type boron nitride crystal layer,

12 np-type boron nitride crystal layers

13 phosphor layer

14, 15 electrodes

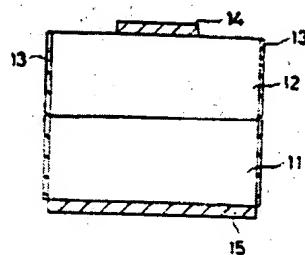


FIG. 1

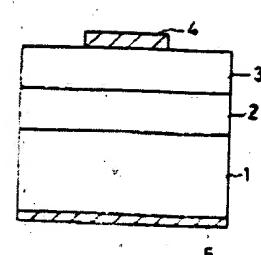


FIG. 2

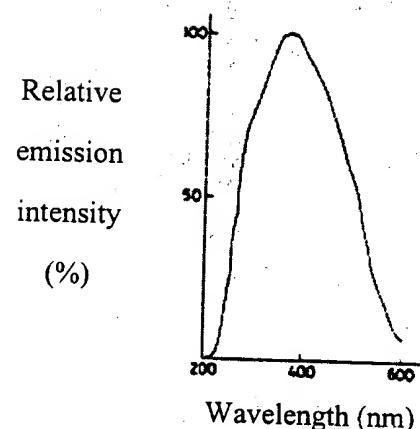


FIG. 3

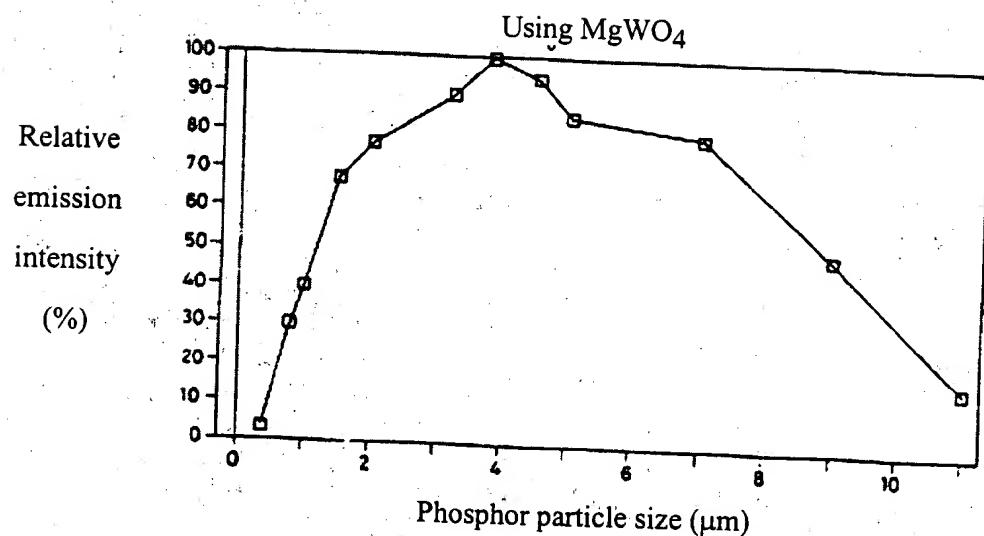


FIG. 4

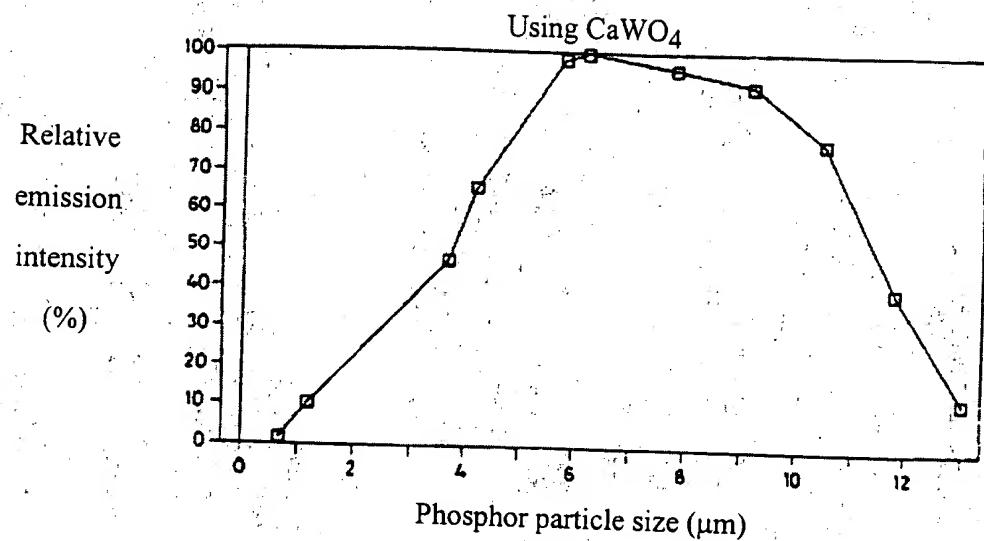


FIG. 5

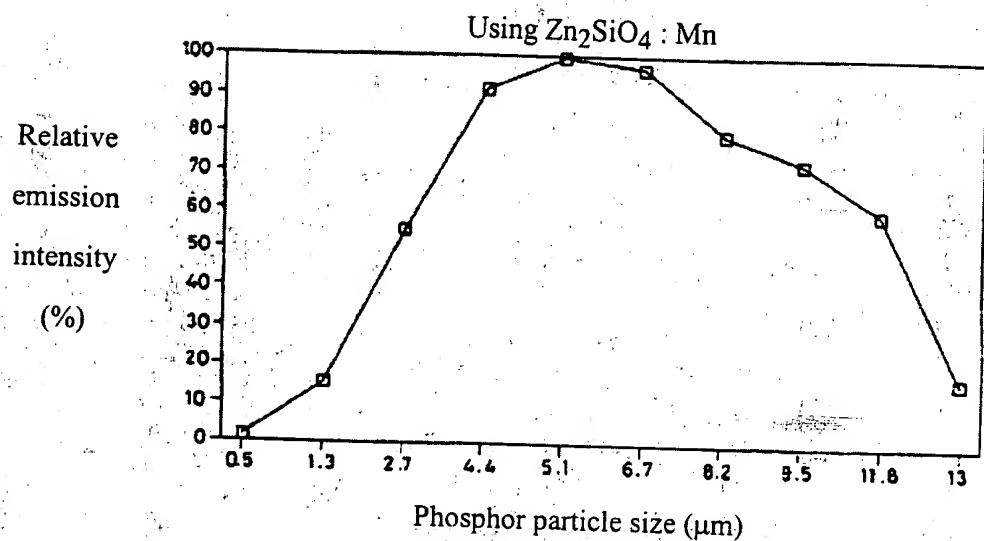


FIG. 6

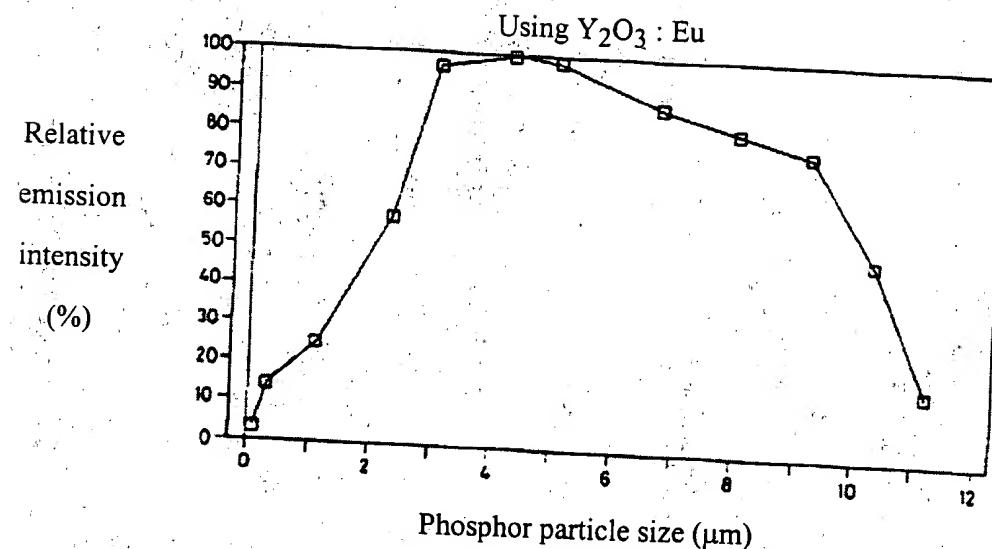


FIG. 7

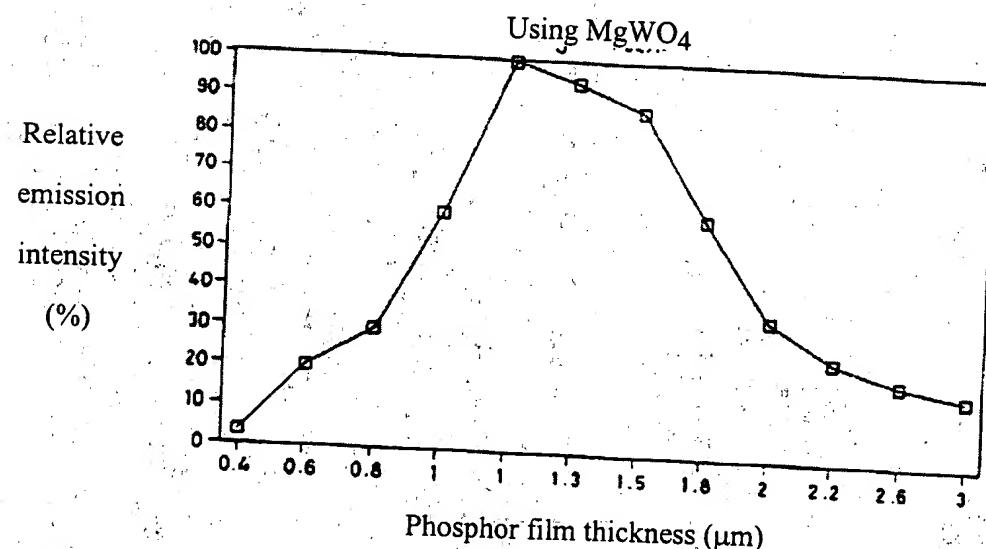


FIG. 8

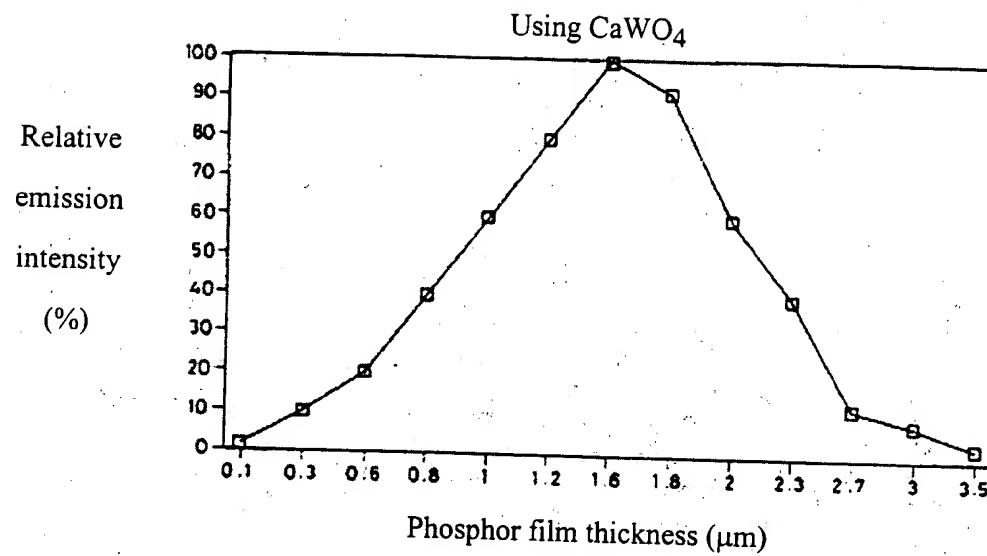


FIG. 9

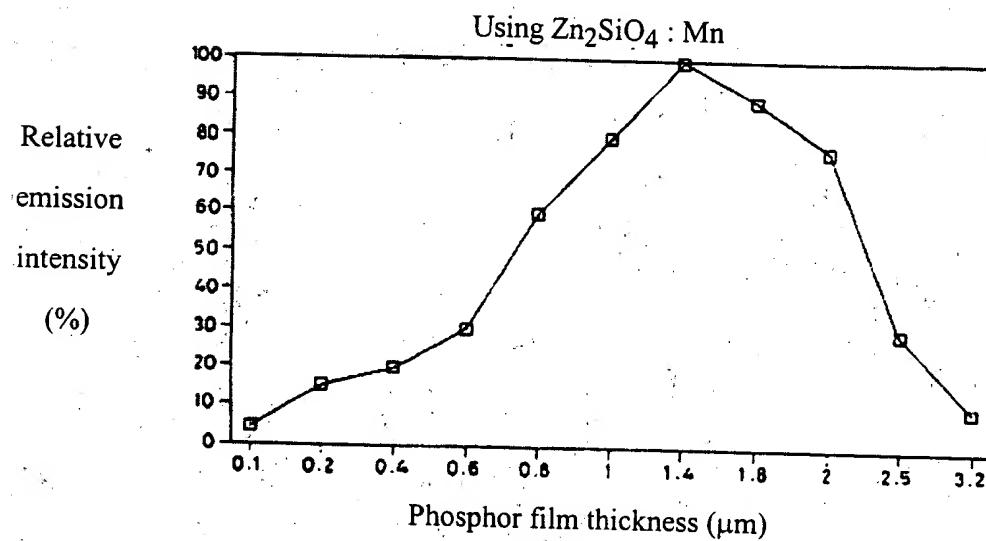


FIG. 10

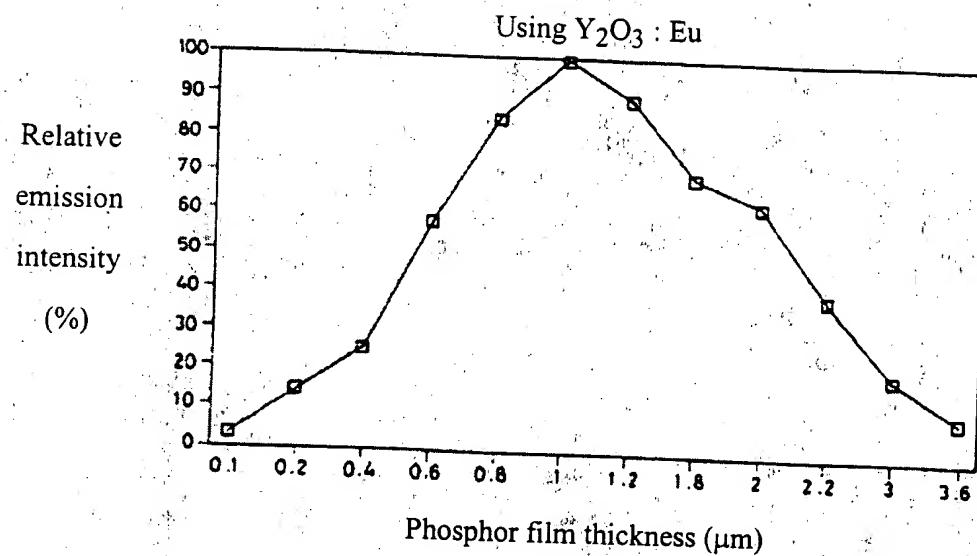


FIG. 11